

EAST Search History**EAST Search History (Prior Art)**

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|---|------------------------------|------------------|---------|---------------------|
| L1 | 535769 | @pd> "20090101" | US-PGPUB; USPAT; USOCR | OR | ON | 2010/01/19 10:01 |
| L2 | 27 | (method and semiconductor and device and form and first and second and gate and electrode and (insulat\$3 or dielectric) and (layer or film) and source and drain and organic and material and etch).clm. | US-PGPUB; USPAT; USOCR | OR | ON | 2010/01/19 10:01 |
| L3 | 5 | 1 and L2 | US-PGPUB; USPAT; USOCR | OR | ON | 2010/01/19 10:01 |

1/ 19/ 2010 10:01:50 AM**C:\ Documents and Settings\ aho1\ My Documents\ EAST\ Workspaces\ 10573328.wsp**